

Application Serial No.:  
10/646,409

Attorney Docket No.:  
SP03-108

a) Amendments to the Specification

*Please amend paragraph [0008] as follows:*

[0008] U.S. Pat. No. ~~S,475,575B1~~ 6,475,575B1 to Ikuta et al. (hereinafter Ikuta et al.) discloses a hard pellicle having a synthetic quartz pellicle layer and a method for making such pellicle. The pellicle layer is required to have less than 100 ppm of OH concentration and to be substantially free of oxygen deficient defect. The specification to meet the requirement of transmission and wavefront distortion with respect to thickness uniformity and sag are difficult to meet. Also, the method disclosed in Ikuta et al. involves forming a discrete sheet of pellicle layer by, for example, thinning and polishing of a fused silica body, followed by cutting and mounting of the pellicle layer to a pellicle mount frame. Making a complete pellicle comprising a thin pellicle layer having a thickness lower than 120  $\mu\text{m}$  mounted to a frame is not practical using the method of Ikuta et al.